





PHOTOSENSITIVE LITHOGRAPHIC PLATE

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Abstract of JP59053836

PURPOSE: To improve stability of sensitivity during plate making, by using a combination of a photopolymerizable compsn. contg. a specified photosensitive polymer and a diazo resin.

CONSTITUTION: A photopolymerizable compsn. layer formed on at least one side of a support consists of (A) a polymer having in the side chains unsatd. groups, each represented by the general formula, and a carboxyl group, (B) a monomer or oligomer having at least two polymerizable ethylenically unsatd. double bonds on the basis of monomer, (C) a photopolymn. initiator, and (D) a diazo resin, such as 2-methoxy-4-hydroxy-5-benzoyl-benzenesulfonate produced by condensation of 4-diazo-diphenylamine and formaldehyde. As (B), pentaerythritol tetraacrylate, etc. are used, and as (A), allyl methacrylate/methacrylic acid copolymer in 85/15 molar ratio, etc. are used.

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